Study Of ESD Effects On RF Power Amplifiers

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STUDY OF ESD EFFECTS ON RF POWER AMPLIFIERS

by

DIVYA NARASIMHA RAJU
B.S. Visvesvaraya Technological University, 2006

A thesis submitted in partial fulfillment of the requirements
for the degree of Master of Science
in the Department of Electrical Engineering and Computer Science
in the College of Engineering and Computer Science
at the University of Central Florida
Orlando, Florida

Spring Term
2011
ABSTRACT

Today, ESD is a major consideration in the design and manufacture of ICs. ESD problems are increasing in the electronics industry because of the increasing trend toward higher speed and smaller device sizes. There is growing interest in knowing the effects of ESD protection circuit on the performance of semiconductor integrated circuits (ICs) because of the impact it has on core RF circuit performance.

This study investigated the impact of ESD protection circuit on RF Power amplifiers. Even though ESD protection for digital circuits has been known for a while, RF-ESD is a challenge. From a thorough literature search on prior art ESD protection circuits, Silicon controlled rectifier was found to be most effective and reliable ESD protection for power amplifier circuit. A SCR based ESD protection was used to protect the power amplifier and a model was developed to gain better understanding of ESD protected power amplifiers. Simulated results were compared and contrasted against theoretically derived equations. A 5.2GHz fully ESD protected Class AB power amplifier was designed and simulated using TSMC 0.18 um technology.

Further, the ESD protection circuit was added to a cascoded Class-E power amplifier operating at 5.2 GHz. ADS simulation results were used to analyze the PA’s RF performance degradation. Various optimization techniques were used to improve the RF circuit performance.
Dedicated to My Father
ACKNOWLEDGMENTS

I would like to thank my advisor, Dr. Jiann S. Yuan, for his continuous commitment to help and support me through my graduate career. I wish to express my sincerest gratitude to him for providing me with timely guidance as well as the moral support and encouragement in the research work. I am also thankful to Dr. Kalpathy Sundaram and Dr. Lee Chow for serving on my committee.

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Finally, a special mention must be made to express my deepest gratitude to my husband Narasimha Nagaiah, who supported me with his love for every moment during ups and downs of this work.
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# LIST OF ACRONYMS AND ABBREVIATIONS

<table>
<thead>
<tr>
<th>Abbreviation</th>
<th>Full Form</th>
</tr>
</thead>
<tbody>
<tr>
<td>ADC</td>
<td>Analog-to-Digital Converter</td>
</tr>
<tr>
<td>ADS</td>
<td>Advanced Design System</td>
</tr>
<tr>
<td>CDM</td>
<td>Charged Device Model</td>
</tr>
<tr>
<td>CMOS</td>
<td>Complementary Metal Oxide Semiconductor</td>
</tr>
<tr>
<td>DAC</td>
<td>Digital-to-Analog Converter</td>
</tr>
<tr>
<td>DE</td>
<td>Drain Efficiency</td>
</tr>
<tr>
<td>ESD</td>
<td>Electrostatic Discharge</td>
</tr>
<tr>
<td>GGNMOS</td>
<td>Gate Grounded NMOS</td>
</tr>
<tr>
<td>HBM</td>
<td>Human Body Model</td>
</tr>
<tr>
<td>HHSCR</td>
<td>High Holding voltage SCR</td>
</tr>
<tr>
<td>IC</td>
<td>Integrated Circuit</td>
</tr>
<tr>
<td>KVL</td>
<td>Kirchhoff’s Voltage Law</td>
</tr>
<tr>
<td>LNA</td>
<td>Low-noise Amplifier</td>
</tr>
<tr>
<td>MM</td>
<td>Machine Model</td>
</tr>
<tr>
<td>MLSCR</td>
<td>Modified Lateral SCR</td>
</tr>
<tr>
<td>MOSFET</td>
<td>Metal-Oxide Semiconductor Field Effect Transistor</td>
</tr>
<tr>
<td>NMOS</td>
<td>n-Channel Metal Oxide Semiconductor</td>
</tr>
<tr>
<td>PA</td>
<td>Power Amplifier</td>
</tr>
<tr>
<td>PAE</td>
<td>Power Added Efficiency</td>
</tr>
<tr>
<td>RF</td>
<td>Radio Frequency</td>
</tr>
<tr>
<td>RH</td>
<td>Relative Humidity</td>
</tr>
<tr>
<td>SCR</td>
<td>Silicon Controlled Rectifier</td>
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</tbody>
</table>
CHAPTER ONE: INTRODUCTION

Wireless communication revolution is at its peak like never before and is evident from the fast, compact and affordable smart phones available in market today. The growing dependency on these devices has increased reliability concerns and thus constant effort has been put to ensure all products are highly reliable and can withstand severe electrostatic discharges. With the increasing speed and decreasing size of devices, there will always be new ESD related concerns rising and more challenges to be faced.

Need for ESD

ESD has become the primary reliability concern in modern integrated circuits (IC). An IC can be subjected to ESD zapping at various places, right from fabrication room to end-user. Especially, thinner gate oxides and shallower diffusion junction increase the risk of ESD damage. A 1999 study estimates that up to 30% of all CMOS failures can be attributed to ESD damage and that ESD related damage has cost the IC industry billions of dollars [1], thus ESD related concerns can no longer be ignored. Precautions have been taken to avoid any electrostatic discharge during manufacturing process. However, for an IC to be reliable, it should be able to handle the ESD stress at any point. Therefore, incorporation of ESD protection circuit in the semiconductor chip is vital. The main focus is to identify the ESD susceptible devices and protect them. Designers should also test and characterize their circuits to ensure that the IC’s are immune to severe ESD events.
RF-ESD

ESD protection circuits have been intensely researched for a while now, especially for Digital IC’s. Research shows that very reliable ESD protection circuits are available for Digital IC’s like high speed interface circuits. As and when integration of RF circuits into CMOS IC’s became familiar, an interesting yet very challenging field of research called “RF-ESD” was introduced. Even though ESD protection circuit design was well known, RF-ESD has its own concerns due to fact that addition of ESD protection circuit degrades RF circuit performance significantly. Shown in Figure 1.1 is transceiver block diagram and it indicates that the two blocks highly susceptible to ESD events are LNA and PA and hence needs to be protected.

![Transceiver Block Diagram](image)

Figure 1.1: General overview of a transceiver circuit

ESD protection circuit design principle for RF circuits is different from that of digital circuitry. Figure 1.2 shows the RF-ESD circuit design flow. Some of the key concepts to be kept in mind while designing RF-ESD are as follows. Firstly, the protection circuit for RF-ESD may be a function of the application frequency. Below 1 GHz, a conventional digital ESD protection
circuit can be used. Whereas, between 1GHz to 5 GHz, ESD versus RF optimization is required and for 5GHz to 15GHz, RF-ESD co-design becomes mandatory. Secondly, Unlike in Digital applications where the primary focus is on dc voltage shift and leakage, RF-ESD focuses on RF circuit performance degradation. For example, when diode is used ESD protection in digital circuits, the primary concern is differential voltage isolation whereas in case of RF-ESD, it will be capacitive coupling and stability. Lastly, the distinction between RF-ESD design and Digital ESD design is circuit failure evaluation. In digital ESD, dc leakage alone determines failure criteria whereas RF-ESD requires evaluation of many parameters like RF parameters, dc parameters and system level requirements [2].
Motivation

Development of high speed, high performance RF circuits make it highly sensitive and susceptible to ESD stress, also due to downscaling of CMOS technology. This makes ESD protection circuit most integral part of design and manufacture of reliable IC’s. In spite of
researching ESD protection circuits for a longtime, it is a continuous struggle to find optimum solution which will have zero impact on RF core circuits. In an effort to achieve this, we have designed an ESD protected power amplifiers which will be explained in detail in the following chapters. Optimization of the circuit will aid in improving circuit performance, however implementing an effective ESD protection without disturbing the core RF circuit performance is nearly impossible for now.

Goals and Outline

The ultimate goal of this research is to study the impact of ESD protection circuit on the RF power amplifiers by modeling, simulating and finally optimizing to reduce the performance degradation. Designs are simulated and verified using MATLAB and ADS tools.

The Introduction in Chapter One has presented the importance of RF-ESD and key concerns associated with RF-ESD. In Chapter Two, the fundamental of ESD and test models such as HBM, MM are explained in brief. Chapter Three details the available device level solution for ESD protection. Further, it will introduce the Modified Lateral SCR and High Holding voltage SCR, the two devices used for ESD protection of RF power amplifiers as part of this thesis, along with the reason why the SCR is chosen for ESD protection. Chapter Four will discuss the basics of power amplifier design and explain the model derivation of the partially protected Class-A PA using the analytical understanding backed by fundamental equations describing circuit behavior. It also covers the design and simulation of fully ESD protected Class AB power amplifier. This chapter also includes ESD protection for Switch mode Class E PA and its optimization. The thesis finally concludes with Chapter Five and Chapter Six discussing the conclusion and future work respectively.
References


CHAPTER TWO: ELECTROSTATIC DISCHARGE

Electrostatic Discharge (ESD) is the discharge of static electricity. Static electricity is an excess or deficiency of electrons on one surface with respect to another surface or to ground. A surface exhibiting an excess of electrons is negatively charged, and an electron deficient surface is positively charged. When a static charge is present on an object, the molecules are electrically imbalanced. Later the static charge moves from one surface to another with different potential resulting in ESD. Electrostatic-Discharge (ESD) takes place when a re-establishment of equilibrium is attempted through the transfer of electrons between one object and another that is at a different voltage potential. As an example, we experience Static electricity when we touch a door knob after walking on carpeted floor. Table 2.1[1] shows examples of static electricity generation. Similarly, an IC can be subjected to an ESD event in the following ways: a charged body can touch an IC, a charged IC can touch a grounded surface, a charged machine can touch an IC, or an electrostatic field can induce a voltage across a dielectric sufficient to break it down. While human nervous system can’t sense the static discharge below 3500 volts, a several hundred volts is high enough to destroy the entire IC. For example, Consider a 0.18μm CMOS technology with gate oxide thickness is 40Å which can sustain electric field up to 10MV/cm. Under supply voltage of 2.4V, the maximum allowed DC voltage that can be applied across the gate oxide is just 4V.
Table 2.1: Example of Static Charge Generation

<table>
<thead>
<tr>
<th>Means of static generation</th>
<th>RH 10-20%</th>
<th>RH 65-90%</th>
</tr>
</thead>
<tbody>
<tr>
<td>Walking across a carpet</td>
<td>35,000V</td>
<td>1,500V</td>
</tr>
<tr>
<td>Walking on a vinyl tile floor</td>
<td>12,000V</td>
<td>250V</td>
</tr>
<tr>
<td>Vinyl envelopes for work instructions</td>
<td>7,000V</td>
<td>600V</td>
</tr>
<tr>
<td>Worker at bench</td>
<td>6,000V</td>
<td>100V</td>
</tr>
</tbody>
</table>

ESD Induced Failures

When an ESD-sensitive device becomes part of the discharge path, or is under the influence of high electrostatic field, it can be permanently damaged. The ESD sensitivity level varies depending on device and technology. Table 2.2 shows the sensitivity of various devices to ESD damage.

Table 2.2: Sensitivity of Electronic Devices to Damage by ESD

<table>
<thead>
<tr>
<th>Device</th>
<th>Damage Susceptibility Voltage Range</th>
</tr>
</thead>
<tbody>
<tr>
<td></td>
<td>Damage begins occurring at</td>
</tr>
<tr>
<td>MOSFET</td>
<td>10</td>
</tr>
<tr>
<td>VMOS</td>
<td>30</td>
</tr>
<tr>
<td>NMOS</td>
<td>60</td>
</tr>
<tr>
<td>GaAsFET</td>
<td>60</td>
</tr>
<tr>
<td>EPROM</td>
<td>100</td>
</tr>
<tr>
<td>JFET</td>
<td>140</td>
</tr>
<tr>
<td>SAW</td>
<td>150</td>
</tr>
<tr>
<td>Op-AMP</td>
<td>190</td>
</tr>
<tr>
<td>CMOS</td>
<td>200</td>
</tr>
<tr>
<td>Schottky Diodes</td>
<td>300</td>
</tr>
<tr>
<td>Film Resistors</td>
<td>300</td>
</tr>
<tr>
<td>This Film Resistors</td>
<td>300</td>
</tr>
<tr>
<td>ECL</td>
<td>500</td>
</tr>
<tr>
<td>SCR</td>
<td>500</td>
</tr>
<tr>
<td>Schottky TTL</td>
<td>500</td>
</tr>
</tbody>
</table>
Depending on how sensitive the device is, an ESD event can cause catastrophic/hard failure or Latent/soft failure. Catastrophic failure is when the device stops functioning and has been destroyed permanently. Where as in case of latent failure, the device seems to perform normally but may not be reliable anymore. Some of ESD induced failures are:

1. **Dielectric Breakdown**: This is a predominant failure mechanism on MOS devices when the voltage across the oxide exceeds the dielectric breakdown strength. This failure mechanism is basically voltage dependent where the voltage must be high enough to cause dielectric breakdown. As such, the thinner the oxide, the higher the susceptibility to ESD.

2. **Thermal Runaway (Second Breakdown)**: This failure mechanism results in junction melting when the melting temperature of silicon (1415°C) is reached. This is basically a power dependent failure mechanism; the ESD pulse shape, duration and energy can produce power levels resulting in localized heating and eventually junction melting, even though the voltage level is below that required to cause dielectric breakdown.

3. **Parametric Degradation**: On precision, high speed ICs ESD can cause device degradation, besides functional failures. This can impact electrical performance and adversely affect device reliability. This degradation in device parametric performance is far more difficult to pinpoint as an ESD related failure mode. It is also the least understood among the failure modes. The extent of this degradation is dependent on the number of ESD pulses and the level of damage sustained [2].
ESD Test Models

ESD can have serious detrimental effects on all semiconductor ICs and the system that contains them. ESD events are by nature, unpredictable, a number of models have been developed to characterize different ESD scenarios and events. These standard models help us to enhance the quality and reliability of ICs by ensuring all devices employed have undergone proper ESD design and testing, thereby minimizing the detrimental effects of ESD. Three major test models are described below in detail.

1. Human Body Model (HBM): This model represents the ESD event “Discharge to the device”. In other words, when a charged human being touches the IC, there is direct transfer of electrostatic charge from human body to the ESD sensitive device. The HBM circuit model consists of capacitor which discharges through resistor and inductor. The transient ESD pulse generated by this model has discharge current level of about 4A with rise time of 10ns and discharge time of 150ns as shown in Figure 2.1.

![Figure 2.1: Human body model circuit and corresponding waveform](image.png)
2. *Machine Model (MM)*: Originated in Japan as a result of investigating worst-case scenarios of the HBM, the Machine Model simulates the transient discharge of a charged machine through the DUT and is represented by the lumped circuit shown in Figure 2.2. The MM is a damped sinusoidal oscillating current waveform, and the time to the first current peak is typically 15ns with duration for the pulse of approximately 40ns.

![Machine Model circuit and corresponding waveform](image)

**Figure 2.2:** Machine Model circuit and corresponding waveform

3. *Charged Device Model (CDM)*: This ESD test model is used to simulate “Discharge from the device”. A device can accumulate charge in a variety of ways, especially in situations where they undergo movement while in contact with another object, such as when sliding down a track or feeder. If they come into contact with another conductive body that is at a lower potential, it discharges into that body. Such an ESD event is known as Charged Device Model ESD and is highly destructive because of its high current, despite its shorter pulse duration. Figure 2.3 shows the electrical model of CDM event and corresponding waveform.
Figure 2.3: Charged Device Model circuit and corresponding waveform

As MM is just a severe case of HBM, CDM and HBM are much widely used to test for ESD events. The typical values of resistor, capacitor and inductor of the three circuit models (HBM, MM, and CDM) are as shown in the Table 2.3.

<table>
<thead>
<tr>
<th>ESD Test Models</th>
<th>Voltage(V)</th>
<th>R(Ω)</th>
<th>C(pF)</th>
<th>L(µH)</th>
<th>Pulse duration (ns)</th>
<th>Rise time (ns)</th>
<th>Peak current (A)</th>
</tr>
</thead>
<tbody>
<tr>
<td>HBM</td>
<td>2k</td>
<td>1.5K</td>
<td>100</td>
<td>7.5</td>
<td>150</td>
<td>2-10</td>
<td>1.33</td>
</tr>
<tr>
<td>MM</td>
<td>200</td>
<td>15</td>
<td>200</td>
<td>1.5</td>
<td>40</td>
<td>10-15</td>
<td>3.5</td>
</tr>
<tr>
<td>CDM</td>
<td>1k</td>
<td>15</td>
<td>6.8</td>
<td>1</td>
<td>1</td>
<td>0.1-0.5</td>
<td>12</td>
</tr>
</tbody>
</table>

**ESD Protection Circuits**

Various ESD protection strategies for RF circuits have been proposed. These strategies not only concentrate on providing robust ESD protection but also give importance to reduce the performance degradation of RF circuit. Some of the few previous works is discussed below.
1. **Low-C**: Diodes are used from I/O pad to $V_{DD}$ and also from VSS to I/O pad to provide ESD discharge path as shown in Figure 2.4(a). Number of diodes is connected in series to reduce the parasitic capacitance.

![Diagram of Low-C ESD protection](image)

Figure 2.4: (a) Low-C, (b) Impedance Cancellation and (c) Impedance Isolation based ESD protection

2. **Impedance Cancellation**: Here inductor is used as an ESD protection device. Most often, Inductor value is chosen by plug and play. Also, the inductor and parasitic capacitance of the RF core circuit resonate at operating frequency providing maximum shunt impedance. This ESD protection is as shown in Figure 2.4(b).

3. **Impedance Isolation**: As shown in Figure 2.4(c), LC tank in series with diode is used as ESD protection circuit. Similar to Impedance cancellation, the LC tank is made to resonate at RF circuit operating frequency to minimize the negative impact of ESD on core circuit [3].
References


CHAPTER THREE: SCR BASED ESD PROTECTION

Even though there are many ESD protection circuits readily available, ESD design engineers face difficulty in finding a robust ESD protection circuit. Here, the main goal is not only to achieve required level of protection but also minimize the impact it has on the core RFIC performance. A conscious effort is needed to choose ESD protection unit with less parasitics, smaller area and good ESD robustness. After intense study on various ESD protection devices and circuits, Silicon controlled rectifier was found to be the promising candidate for ESD protection of RF power amplifier. The following section defends why SCR was chosen and further explains the on-chip ESD protection scheme in detail.

ESD Protection Devices

An ideal ESD protection device should be capable of providing a conductive path to discharge the ESD current safely without disturbing the core circuit. The most important properties an ideal ESD protection device must possess are described as follows. Firstly, the device should be able to turn on instantaneously when ESD event occurs and should be in off state during normal operation. It should also have zero resistance during ESD, in order to shunt the ESD current as quickly as possible without any voltage drop. Secondly, in order to avoid the unintentional triggering of the protection device, the sustaining voltage of the device must be always greater than the supply voltage of the chip. Thirdly, the ideal device must be transparent meaning should have no parasitics so that it will not interfere with core circuit performance. Lastly, the ESD protection device must be reliable and should be capable of surviving the ESD
stress. It is also vital that the ESD protection device size is minimum, so that it does not increase the overall chip area.

**ESD Design Window**

ESD design window aids in defining the boundaries of ESD protection device operation. ESD design window is determined by the operation voltage, oxide breakdown voltage and thermal failure effects. Design window may vary depending on the ESD protection device operating characteristics. However, there are some common key considerations required to understand the ESD design window and are explained in brief as follows. The triggering or turn-on voltage ($V_t$) must be greater than core circuit operating voltage in order to avoid false triggering and it must be lower than breakdown voltage of core circuit. It is important to design the holding voltage ($V_H$) of protection device to be greater than supply voltage to avoid any unnecessary latch up issues. In addition, it is necessary to keep failure current ($I_{t2}$) as high as possible for good robustness.

![Figure 3.1: ESD design window](image-url)
Figure 3.1 shows the ESD design window for SCR as the protection device. ESD design window depends merely on the core circuit design specifications and technology used. With shrinking gate oxides, the ESD design windows are becoming narrower making it hard for ESD design engineers to create an effective ESD protection strategy.

**Prior Art ESD Protection Devices**

The basic ESD protection devices used can be broadly classified as non-snapback and snap back devices. Diode is best example of non-snapback device. It is called non-snapback device because beyond certain voltage, with increase in the voltage, the current increases but voltage across it remains constant. Diode can be used in both forward and reverse mode, however it shows poor ESD performance in reverse direction due to high resistance and breakdown voltage. Non-snapback devices are preferred for the reason that they are not process sensitive and require simple simulators like PSpice. However, the main drawback of using diodes for ESD protection is high parasitic capacitance due to large area.

The second category of ESD protection devices are Snapback devices. These devices once turned on, switch from high voltage-low current mode to high current- low voltage mode. This snapback makes the device capable of carrying large current with less power dissipation. In CMOS technology, the two well known snapback devices are ground gated NMOS (ggNMOS) and silicon controlled rectifier (SCR). As the name suggests in ggNMOS, the gate and the source of the MOSFET are tied to ground. The snapback action of this device can be attributed to the parasitic bipolar transistor present in ggNMOS. Some of the major issues using ggNMOS for ESD protection are gate oxide breakdown at high voltages, uniform triggering. Some studies offer solution using techniques like Silicide blocking but requirement of additional process steps
makes it expensive. SCR is another snapback device and has become the favorite choice among ESD designers. While diode and ggNMOS are unidirectional devices (not ESD robust in reverse direction), SCR can conduct ESD current efficiently in both directions. SCR is discussed in detail in the following section, along with the reason why it has been chosen for ESD protection of power amplifiers.

Why SCR?

Silicon Controlled Rectifier has a pnnp structure with two parasitic transistors. It is commonly known as thyristor and the structure is as shown in Figure 3.2. The SCR is triggered by turning on of parasitic npn bipolar transistor due to avalanche breakdown generated current. Further, the feedback mechanism as shown in the equivalent circuit keeps both the bipolar transistors on and therefore SCR has the capability to switch from high impedance state to low impedance state.

![Figure 3.2: Basic structure of SCR and its equivalent circuit](image)

Figure 3.2: Basic structure of SCR and its equivalent circuit
SCR can conduct very high current with very low on resistance mainly due to its almost ideal conductivity modulation profile. SCR provides full voltage swing, meaning it can efficiently discharge ESD current in both directions. In addition to it, it has low parasitic capacitance, higher $I_{2}$ and smaller area makes it a favorable choice for ESD protection. However, it has some issues like the higher first breakdown voltage and lower holding voltage (causes latch up) which has to be resolved. Literature search reveal various modified SCR’s which tackle these shortcomings to some extent making SCR most preferred ESD protection device.

There are few previous research papers which have presented ESD protection for power amplifiers. Reference [1] and [2] uses inductance in parallel at the PA output stage. Inductance discharges ESD current acting as short circuit during ESD event and acts as open circuit during RF circuit operation. However, the main drawback of this technique is large area occupied by inductor. Reference [3] uses waffle-structured SCR for major ESD current between output pad and $V_{SS}$ and also for power clamp circuit. This protection circuit uses additional RC triggering circuit for SCR. The ESD protection technique presented in this paper provides high ESD robustness, protecting PA from ESD events in all directions (PS, NS, PD and ND). However, the main drawback is that the output swing (range) is limited by the diodes present between output pad and $V_{DD}$ ($V_{O} < V_{DD} \times 2 \times V_{on}$).

**Implementation of On-Chip ESD Protection**

The basic idea behind on-chip ESD protection for CMOS IC’s is to provide a highly conductive ESD current discharge path without disturbing the core circuit. Here, the concept of ESD protection for RFIC’s is explained with reference to RF power amplifiers, which is the main
goal of this thesis. ESD events occur between two pins at different potential. To protect the core RF circuit from being destroyed by ESD event, we need to provide a safe low impedance path for ESD current to discharge. Therefore, it is important to first identify the ESD sensitive pins/ports and then implement a protection circuit for it.

In this typical application, the RF power amplifier input is output of the higher level as shown in Figure 1.1. As the RF input terminal is embedded inside a chip, there is no danger for static electricity damage. In contrast, the output of power amplifier is directly connected to antenna and hence is at high risk of electrostatic discharge. In current scenario, the RF output, power supply and ground terminal require ESD protection circuit. Figure 3.4 shows the ESD protection scheme for RF power amplifier. For better understanding of the strategy used in ESD protection of power amplifier we need to get familiarized with various ESD zapping modes shown in Figure 3.3.
In general, ESD pulses can be applied in various directions like, from output pad to power supply and vice versa, from output pad to ground and vice versa and from power supply to ground and vice versa. The following section explains each zapping mode in detail, along with the ESD current discharge path provided for each kind of ESD pulse as shown in Figure 3.4.
Figure 3.4: Schematic Diagram of ESD protection for RF power amplifier

1. **PS mode:** A positive voltage ESD stress occurs between output pin with $V_{SS}$ grounded and all other pins floating. The discharge path for this ESD pulse is provided by first MLSCR (explained later) present between output pin and ground.

2. **NS mode:** A negative voltage ESD stress occurs at output pin with $V_{SS}$ grounded and all other pins floating. The second MLSCR between $V_{SS}$ and output pin provides the ESD current discharge path protecting the RF circuit.

3. **PD mode:** A positive voltage ESD stress occurs at output pin, while $V_{DD}$ is grounded and all other pins including $V_{SS}$ is floating. The ESD current discharges to $V_{DD}$ through the first MLSCR and the parasitic diode present in the HHSCR (discussed later).
4. **ND mode:** A negative ESD stress occurs between output pin and grounded \( V_{DD} \) while rest of the pins including \( V_{SS} \) is floating. Here, the transient ESD current is discharged by third MLSCR present between \( V_{DD} \) and output pin.

5. **DS mode:** The discharge path between \( V_{DD} \) and \( V_{SS} \) is provided by HHSCR, thereby achieving the complete ESD protection of RF circuit.

The isolation capacitance seen in Figure 3.14 between PA and protection circuit acts as a decoupling capacitor. A higher ESD voltage may be induced by current conduction via SCR and this overshooting voltage may be greater than drain breakdown voltage. Therefore, isolation capacitance is needed to block any direct connection between RF PA and ESD protection circuit.

**I/O Pad ESD Protection**

As explained in previous section, Modified Lateral SCR was chosen for the ESD protection of the output pad of RF power amplifier. Figure 3.5 shows the cross section of MLSCR. MLSCR is referenced from the work by Javier A. Salcedo, UCF. It is similar to conventional SCR structure except for addition p+ region between n-well and p-well. Now, the p+/n-well will be the blocking junction instead of n-well/p-well. Since p-well is less doped than n-well, p+/n-well is chosen to achieve lower trigger voltage. It can be observed that n+ region at anode has been removed. With n-well floating, the collector current increases, thereby increasing the gain and further decrease of triggering voltage. Higher holding voltage can be achieved by increasing the D4 value shown in Figure 3.5.

In order to avoid false triggering of MLSCR, it is very important to note that forward and reverse triggering of MLSCR is greater than forward and reverse pad voltage (full voltage swing).
but should be less than secondary breakdown voltage. However, the holding voltage can be less than output pad voltage as the current at the pad is lower and cannot sustain latch-up.

![Cross-sectional view of MLSCR](image)

**Figure 3.5: Cross-sectional view of MLSCR**

The device size required to carry ESD current is dependent on test model. For HBM ESD level of 2 kV, $V_{HBM} = (R_{ON} + R_{HBM})I_{t2}$. With $R_{HBM}= 1.5k\Omega$, $R_{ON} << R_{HBM}$ and therefore $I_{t2} = 1.33A$. Knowing that the current carrying capability of SCR is approximately, 70mA/µm, we can easily calculate the required device size. Here, each MLSCR has 4 fingers, 50µm each and thus can carry worst case ESD current of 14A providing protection for HBM level of 21kV.

**Power Supply Clamp**

SCR chosen for power clamp needs to have higher holding voltage due to two reasons: (1) Due to lower holding voltage, SCR can be triggered during normal operation and (2) Once the SCR discharges ESD current it should turn off, but this may not happen if holding voltage is lower than supply voltage. Therefore, to avoid latch up problem, holding voltage $V_H > 1.4 \times$
With these considerations in mind, HHSCR was found to be aptly suitable for this application. The HHSCR structure shown in Figure 3.6 is referenced from the work done by Qiang Cui, UCF. Holding voltage is the voltage drop between anode and cathode of SCR, which is required to maintain SCR’s conductivity modulation. In order to increase the holding voltage, three diodes has been added between Anode and emitter of pnp transistor. Now, \( V_H = V_R + V_{CE} + 3 \times V_D \). Voltage drop across each diode, \( V_D \) can be approximately 1V, hence the name high holding voltage SCR. The parasitic diode present in HHSCR aids in PA output pad protection.

\[
V_H = V_R + V_{CE} + 3 \times V_D
\]

![Cross-sectional view of HHSCR](image)

**Figure 3.6: Cross-sectional view of HHSCR**

**ESD Parasitics Modeling**

Once we have the suitable ESD protection device, we need to determine the parasitics of the device. The S-parameter measurement results given by device engineers are used to estimate the device parasitics. A model is required to analyze the effect of ESD protection circuit on RF circuits. Depending on the impact the ESD device has on core circuit, optimization of core
circuit can be done to improve the results. Further, using this model the transient analysis can be performed to verify the HBM ESD robustness.

In order to extract the parasitics of SCR device, a simple RC model is used. As per the ESD protection scheme discussed before, a single SCR is used between output pad and power supply. However, we have two SCR’s in parallel between output pad and ground. Therefore, the final value of resistance and capacitance is two corresponding resistances and capacitances in parallel as shown in Figure 3.7. The parasitics of SCR is calculated from Y-parameter by using the following equation.

\[ Y = G + j.B \]  \hspace{1cm} (3.1)

The parasitics resistance of SCR device RC MODEL is calculated using
The parasitic capacitance is extracted by using the following equation at frequency of 5.2GHz.

$$R_{ESD} = \frac{1}{\text{Real}(Y_{21})}$$ (3.2)

Two set of resistance and capacitance values were calculated, one for ESD protection between power supply and output pad. Another set of RC values for ESD protection between output pad and ground. The values are as shown in Table 3.1. To verify the RC values extracted, an S-parameter measurement of RC model with calculated values was done using ADS simulation. Results of both device simulation and ADS simulation are compared in Table 3.2.

Table 3.1: Calculated parasitic Resistance and Capacitance values of RC model

| C1+C2   | R1||R2  | C3    | R3    |
|---------|-------|-------|-------|-------|
| 0.386 pF | 549 Ohm | 0.208 pF | 947 Ohm |

Table 3.2: Comparison of S-parameters obtained from SCR device simulation and ADS simulation of RC model

<table>
<thead>
<tr>
<th></th>
<th>S21</th>
<th>S11</th>
</tr>
</thead>
<tbody>
<tr>
<td>Device Simulation</td>
<td></td>
<td></td>
</tr>
<tr>
<td>MLSCR Single</td>
<td>0.34+j0.42</td>
<td>0.65-j0.42</td>
</tr>
<tr>
<td>MLSCR Pair</td>
<td>0.58+j0.43</td>
<td>0.41-j0.43</td>
</tr>
<tr>
<td>ADS Simulation</td>
<td></td>
<td></td>
</tr>
<tr>
<td>MLSCR Single</td>
<td>0.34+j0.404</td>
<td>0.65-j0.404</td>
</tr>
<tr>
<td>MLSCR Pair</td>
<td>0.604+j0.422</td>
<td>0.396-j0.422</td>
</tr>
</tbody>
</table>
References


CHAPTER FOUR: ESD PROTECTED POWER AMPLIFIERS

Power Amplifier (PA) is an important candidate of the wireless transceiver. The RF power amplifier is used to amplify the RF signal being transmitted to an adequate power level such that it can propagate over a required distance through the wireless channel. In order to meet the growing demands of low cost, low power and high capacity, CMOS process technology is being widely used to implement RF-PA. In general, there is tradeoff between characteristics like amplifier’s linearity and efficiency. Improving amplifier’s linearity will degrade its efficiency.

The standard industry defined metrics are used to characterize the performance of a PA. Various metrics that are briefly explained in the following section help us evaluate how efficiently the PA can amplify the signal with minimum distortion.

1. **Output Power**: The output power of an RF power amplifier is defined as the total power of the RF signal delivered by the power amplifier to the load. For Sinusoidal signal, the output power is given by

   \[ P_o = \frac{V_o^2}{2R_L} \]  \hspace{1cm} (4.1)

2. **Efficiency**: Power amplifier efficiency is a metric that indicates how efficiently power drawn from the supply is converted to RF power delivered to the load [1]. Higher efficiency means less power loss in the amplifier. Three most commonly equations used to determine PA efficiency are:

   \[ \text{Power added efficiency, PAE} = \frac{P_o - P_{in}}{P_{dc}} \]  \hspace{1cm} (4.2)
Where, \( P_{dc} = V_{dc}\cdot I_{dc} \) gives the total DC power drawn from the supply, \( P_{in} \) is the power amplifier input power and \( P_O \) is the output power of the amplifier.

3. **Power Gain:** The power Gain of an amplifier is the ratio of the output power to its input power and is given by,

\[
Power \ Gain = \frac{P_O}{P_{in}}
\]  

4. **Linearity:** Linear amplification is required when the signal contains both amplitude and phase modulation. Linearity ensures that the original information is preserved and can be later detected without any error. Depending on the application, Linearity can be quantified using several different techniques such as Intermodulation distortion, 1-dB compression point or third-order Intercept point (IP3).

In general, there is a tradeoff between these characteristics like improving amplifier’s linearity will degrade its efficiency.

**Power Amplifier Classification/classes:** Power amplifiers can be broadly classified into current-mode Amplifiers and switching-mode Amplifiers, based on how the active device behaves. Current-mode amplifiers, also called as transconductance PA, make use of the active device as a transconductor. In this category, the active device acts as a voltage-controlled current source, meaning its output current is controlled by its input voltage. While switching PA, uses the active device as a switch to modulate the output voltage or current. Current-mode PAs
include classes A, AB, B, and C depending on the conduction angle. On the other hand, switching amplifiers are divided into classes D, E and F.

**Modeling of Class-A Power Amplifier with ESD**

Class-A power amplifier is a linear amplifier, where the amplified output voltage is exact replica of input voltage. Figure 4.1(a) shows a basic class-A power amplifier [2]. It consists of a transistor as an amplifying device, RF choke, coupling capacitor and a parallel resonant circuit. The transistor is used as a dependent current source and conducts all the time with conduction angle 360°. At operating frequency, parallel resonant circuit at the load, filters out the harmonics and reduces distortion due to large signal operation [2].

![Class-A Power Amplifier Circuit](image)

**Figure 4.1:** (a) Class-A power amplifier circuit, (b) Class-A PA with ESD protection circuit

In class-A power amplifier, the transistor is operating in active region, with gate to source voltage greater than threshold voltage of the transistor. The Class-A power amplifier with ESD shown in Figure 4.1(b) can be modeled with the following equations.
The drain current of Class-A power amplifier is given by,

\[ i_D(t) = I_{DD} - I_m \sin(\omega t) \]  

(4.6)

where \(I_{DD}\) is the bias current and \(I_{max}\) is the peak sinusoidal current.

\(I_m\) is given by the drain current of an n-channel MOSFET

\[ I_m = \frac{1}{2} \mu_n C_{ox} \left( \frac{W}{L} \right) (V_{GS} - V_t)^2 \text{ for } V_{GS} \geq V_t \text{ and } V_{DS} \geq V_{GS} - V_t \]  

(4.7)

where \(\mu_n\) is the electron mobility in the channel.

\(C_{ox}\) is the oxide capacitance and is given by \(C_{ox} = \varepsilon_{ox}/t_{ox}\)

\(W\) is the channel Width and \(L\) is the channel width.

\(V_{GS}\) is the gate to source voltage

\(V_t\) is the threshold voltage.

The drain voltage at the resonant frequency of the parallel resonant circuit is

\[ v_D(t) = V_{DD} + V_m \sin(\omega t) \]  

(4.8)

where \(V_{DD}\) is the dc supply voltage and \(V_m = I_m \times R_{eff}\). Note that \(R_{eff}\) is the effective load resistance, given by \(R_L\) and \(R_{ESD}\) in parallel.

An ideal parallel- resonant circuit L-C presents an infinite reactance at the resonant frequency \(f_0 = 1/(2\pi\sqrt{LC})\). By applying KCL, the output current at the resonant frequency \(f_0\) is

\[ i_o(t) = I_{DD} - i_D - i_{CESD} \]  

(4.9)

\[ \Rightarrow i_o = I_m \sin(\omega t) - i_{CESD} \]  

(4.10)

The current through the ESD capacitor is

\[ i_{CESD} = 2\pi f C V_{DD} \sin(\omega t + 90) \]  

(4.11)

Finally, the output voltage at the resonant frequency is

\[ v_o(t) = I_m R_{eff} \sin(\omega t) \]  

(4.12)
Given these equations, Class-A power amplifier with ESD can be modeled for given specifications. The class-A PA operating at 5.2GHz with load resistance of 50 ohm, supply voltage of 3.3V and gate voltage of 1.2V was simulated using MATLAB. The ESD resistance and capacitance were assumed to be 549 ohms and 0.386 pf respectively.

For the same specification, a class-A power amplifier circuit was designed in ADS and simulated. The drain current, drain voltage, output current and output voltage waveforms obtained from both MATLAB and ADS simulation was almost identical. Both the simulation results are shown below.

![Figure 4.2: Transient waveforms of Drain voltage (a) MATLAB, (b) ADS](image)

![Figure 4.3: Transient waveforms of Drain current (a) MATLAB, (b) ADS](image)
Figure 4.4: Transient waveforms of Output voltage (a) MATLAB, (b) ADS

Figure 4.5: Transient waveforms of Output current (a) MATLAB, (b) ADS

Figure 4.6: Transient waveforms of ESD Capacitance current (a) MATLAB, (b) ADS
Class-AB Power Amplifier with Full ESD protection

Class-AB power amplifier is a compromise between class-A and class-B in terms of efficiency and linearity. The conduction angle of this amplifier is between 180° to 360°. By controlling the gate bias, the conduction can be varied and hence can operate more like class-A or class-B power amplifier. Figure 2 shows the overall circuit of highly stable class-AB power amplifier. This particular power amplifier circuit design is referenced from a work done by a research group in Taiwan. The power amplifier design consists of Input and output matching network, bias circuit, and Inter-stage matching network. Two stage amplification is used to obtain higher output power. The PA circuit below at operating frequency of 5.2GHz shows appreciable performance with good stability.

Figure 4.7: Complete circuit diagram of fully ESD protected Class-AB PA.
The ESD protection used is an optimized SCR structure targeting for 2kV HBM ESD protection level. As shown in the Figure 4.7, the ESD protection device is modeled with its parasitic capacitor $C_{ESD}$ and parasitic resistor $R_{ESD}$. Also, an isolation capacitance is used between core circuit and the ESD protection circuit. The proposed ESD protected PA was implemented using 0.18μm TSMC CMOS process with 6-Metal TSMC technology library in ADS. A Layout was created using cadence tool as shown in Figure 4.8. The final chip size was 1000x1200 μm$^2$ and the addition of ESD protection circuit did not result in increase of chip area.

Figure 4.8: Layout view of Class-AB PA with ESD protection.
Simulation Results

The ESD protected PA shows comparable degradation in RF power Amplifier performance as shown below.

**Figure 4.9:** Gain and Output Power (a) Without ESD and (b) With ESD protection

**Figure 4.10:** PAE (a) Without ESD and (b) With ESD protection
Figure 4.11: Stability Factor (a) Without ESD and (b) With ESD protection

Figure 4.12: S21 (a) Without ESD and (b) With ESD protection
Results of SCR ESD protected RF power amplifier are compared with the results provided in reference [4]. The author of reference [4] uses Inductor for both ESD protection and for matching network. Comparison results are presented in Table 4.1. This work showed 29.113% degradation in PAE as compared to 41.176% PAE degradation in reference [4].
Table 4.1: Comparison of RF circuit performance with and without ESD protection in this work and reference [4]

<table>
<thead>
<tr>
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<th>Without ESD Protection</th>
<th>With ESD Protection</th>
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<tr>
<td><strong>Ref.</strong></td>
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<td>This work</td>
</tr>
<tr>
<td><strong>Without ESD Protection</strong></td>
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<td>This work</td>
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<tr>
<td><strong>With ESD Protection</strong></td>
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<tr>
<td><strong>Process</strong></td>
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<td><strong>Operating Frequency (GHz)</strong></td>
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<tr>
<td><strong>S11 (dB)</strong></td>
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<td><strong>P1 dB</strong></td>
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<tr>
<td><strong>PAE(%)</strong></td>
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<tr>
<td><strong>Die Size (µm²)</strong></td>
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<td>1000x1200</td>
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</table>

ESD Protected Class-E Power Amplifier

Class-E power amplifier was first introduced by Sokals in 1975. It is a switch-mode amplifier, also called as Class-E dc-ac inverters as the transistor can operate at zero-voltage switching or zero-current switching. The basic circuit of Class-E power amplifier is as shown in Figure 4.14. Here the transistor acts as ideal switch with zero on-resistance and infinite off resistance. In other words, the current and voltage waveforms do not overlap at any point of time, yielding a very low power dissipation and higher efficiency [2]. Thus class-E power amplifier is well known for their simple topology, high efficiency and is definitely the most promising candidate for portable devices.
Figure 4.15 shows an overall circuits diagram of Cascoded Class E power amplifier with ESD protection circuit. Cascode structure is chosen in order to reduce the gate oxide stress on the top transistor. In addition, it also decreases the gate to source voltage of both transistors by sharing it. It was suggested by my colleague Karan Kutty in his work that addition of feedback resistor from gate to drain in the driver stage will improve the efficiency of the amplifier.
Addition of ESD protection circuit to power amplifier circuit does degrade the performance of the RF circuit. The PAE of the Class E power amplifier decreased from 33.5% to 20.171%. Some of the degradation can be attributed to impedance mismatch at the output stage. However, performance of the ESD protected circuit can be improved by circuit optimization. Optimization of two parameters, gate voltage and output capacitance immensely minimized the performance degradation and is discussed in brief as follows.

**ESD Impact as Function of \( V_{gg} \):** Variation of gate voltage of the amplifier stage MOSFET affects the performance of amplifier. Once we add the ESD protection circuit, the optimal value of gate voltage changes as shown in Figure 4.16. By supplying a higher gate voltage, the performance of the amplifier can be increased. Therefore, upon addition ESD protection circuit,
optimization of gate voltage becomes very important. However, the reason behind it wasn’t clear but may be related to zero-voltage switching of power amplifier.

![Without ESD Protection Circuit](image1)

![With ESD Protection Circuit](image2)

Figure 4.16: Effect of gate voltage on ESD protected class-E PA performance

**ESD Impact as function of load capacitance:** As discussed above, even the variation of load capacitance has notable impact on performance of class E PA with ESD. The load capacitance in the output stage of PA is in parallel with parasitic capacitance of ESD protection circuit. This results in increase of overall output capacitance, which may degrade the efficiency of the power amplifier. The solution to this is to decrease the load capacitance of the amplifier, thereby decreasing overall output capacitance. Figure 4.17 depicts the fact that decreasing load capacitance does improve the results of ESD protected class E PA.
Simulation Results

Table 4.2: Comparison of RF performance of Class-E PA, before and after optimization.

<table>
<thead>
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<th>Before Optimization</th>
<th>After Optimization</th>
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<td>Gain (dB) @ 0dB</td>
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<td>S11 (dB)</td>
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<td>PAE(%)</td>
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<tr>
<td>PDE(%)</td>
<td>41.728</td>
<td>24.671</td>
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References


CHAPTER FIVE: CONCLUSION

The preliminary research began with in-depth understanding of various existing ESD protection methods. Later, we implemented already existing ESD protected LNA to study the ESD impact on LNA circuit performance. In the process, the studies revealed that not much research has been done towards ESD protection of RF power amplifiers as compared to LNA. The ESD robustness and the RF circuit performance degradation of all available ESD protection technique was evaluated using RF power amplifier circuit and the results were compared.

As high speed CMOS technologies require ESD protection with high protection level and low parasitics, SCR was found to be ideal choice. SCR offers highest ESD protection level per unit area with low parasitics and smaller area. The modified SCR’s with low triggering voltage for I/O protection and with high holding voltage for supply clamp was chosen for ESD protection of RF power amplifiers. Analytical equations were derived from the ESD protected linear power amplifier model. The numerically solved MATLAB results agreed with the ADS simulated results. Further, a complete ESD protection was implemented to Class-AB power amplifier and circuit simulations were performed using the calculated RC model of SCR. Comparison of PA performance with and without ESD helped in evaluation of ESD effect on RF power amplifiers.

Additionally, the SCR based ESD protection circuit was added to switch-mode Class-E power amplifier. Even though there was considerable degradation in class-E PA performance, the circuit optimization improved the power amplifier results significantly.
CHAPTER SIX: FUTURE WORK

The most significant part of ESD design is testing the ESD protected circuit. The fully protected class-AB power amplifier has to be commercially fabricated and tested with 2kV HBM pulse. The chip can also be used to measure the complete RF circuit performance. The analytical equations derived for ESD protected linear power amplifier model can be used to as base to derive the same for Class-E power amplifier. This model will aid in further optimization of the PA circuit to decrease the ESD circuit impact on amplifier’s performance. Lastly, the ESD protected power amplifier can also be tested for Machine Model ESD robustness.